

REMARKS

Claims 1-9 are pending in this application. Claims 5-8 are withdrawn as directed to a non-elected invention. By this Amendment, claim 1 is amended. The amendment produces no new matter. However, for at least the reasons described below, Applicants assert that all claims are allowable.

Entry of the amendments is proper under 37 CFR §1.116 since the amendments: (a) place the application in condition for allowance (for the reasons discussed herein); and (b) place the application in better form for appeal, should an appeal be necessary. The amendments are necessary and were not earlier presented because, e.g. they are made in response to arguments raised in the final rejection. Entry of the amendments is thus respectfully requested.

Applicants gratefully acknowledges the courtesies extended to Applicants' representative by Examiner Chen in the June 28, 2006 personal interview. The substance of the interview is incorporated into the following remarks.

I. Claims Rejections Under 35 U.S.C. §112

The Office Action rejected claims 1-4 and 9 under 35 U.S.C. §112, second paragraph, asserting they were indefinite. Claim 1 has been amended consistent with the Examiner's suggestion to obviate this rejection. Withdrawal of this rejection is respectfully requested.

II. Claims Rejections Under 35 U.S.C. §103

The Office Action rejected claims 1-4 and 9 under 35 U.S.C. §103(a), asserting they were unpatentable over Mashima (2002/0056415). This rejection is respectfully traversed.

Applicants submit that Mashima fails to disclose at least a method of producing a thin film by plasma CVD on an inner wall surface of a substrate, said substrate having a substantially tubular structure, the method having at least the step of flowing a gas for plasma reaction over said inner wall surface and applying a pulse voltage from a high voltage pulse

source on said substrate without substantially applying a DC bias voltage on said substrate to form said film on said inner wall surface, as recited in independent claim 1.

Instead, Mashima teaches a method of solar cell production which is only known to be effective on, "a component, such as a wafer," having a flat shape. Mashima paragraph 21.

Mashima does not teach or suggest a substrate having a complex shape with a defined inner wall surface. No reference has been cited which teaches or suggests applying the method of Mashima to a substrate having a complex shape with a defined inner wall surface.

Applicants respectfully submit that no art has been cited, alone or in combination, which teaches or suggests all features of independent claim 1. Withdrawal of rejection of independent claim 1 under 35 U.S.C. §103(a) is respectfully requested.

Applicants respectfully submit that the independent claim 1 is allowable. Claims 2-4 and 9 are dependent on independent claim 1, and are allowable for at least that reason, as well as for the additional features they recite. Withdrawal of the rejection of claims 2-4 and 9 under 35 U.S.C. §103(a) is respectfully requested.

III. Conclusion

In view of the foregoing amendments and arguments, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



James A. Oliff
Registration No. 27,075

Donald A. DiPaula
Registration No. 58,115

JAO:DAD/axl

Attachment:

Petition for Extension of Time

Date: July 10, 2006

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

<p>DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461</p>
--